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## Energy Dependence of Angular Patterns of X-rays Generated by 20-35 MeV Rechanneling Electrons in Ultrathick Si Crystals

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In this work the energy dependences of the spots and bands in angular patterns of X-rays generated by 20-35 MeV rechanneling electrons in a 2 mm thick Si crystal are presented. It is shown that such a complicated “background” additional to ordinary bremsstrahlung must be taken into account at studying of X-ray generation in periodic structures created on crystalline substrates because in the some cases the X-rays from rechanneling electrons might be so intensive that could mask the effects defined by the periodic structures.

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